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## **ION GUN**

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An ion gun (3) is described for use in ion beam processing comprising: a) a plasma chamber (5) comprising: wall means defining an evacuable chamber having a first end and a second end; and a dielectric member (10) which extends across the first end of the evacuable chamber; b) gas inlet means (11) for admission to the chamber of a plasma forming gas; c) r.f. emitter (12) means associated with the dielectric member (10) for inductively generating a plasma in the gas in the plasma chamber in use of the ion gun; and d) a control grid structure (6) for extracting ions from plasma in the plasma chamber including a first grid (29) arranged for connection to a positive voltage source and a second grid (30) arranged for connection to a negative voltage source so as to produce an acceleration field for accelerating ions towards and through the second grid of the control grid structure. An ion beam processing apparatus (1) incorporating such an ion gun (3) is also described, as well as an ion beam neutraliser (7).

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